ABSTRACT OF THE DISCLOSURE

BAFFLES AND SUBSTRATE TREATING APPARATUSES INCLUDING THE SAME

Provided is a substrate treating apparatus, which includes a plasma generating part configured to generate plasma, a housing disposed under the plasma generating part, and having a space therein, a susceptor disposed within the housing and supporting a substrate, and a baffle including injection holes injecting the plasma supplied from the plasma generating part, to the substrate. The baffle includes a base in which the injection holes are formed, and a central portion of the base is thicker than an edge thereof.

Fig. 1

